

Semiconductor Materials

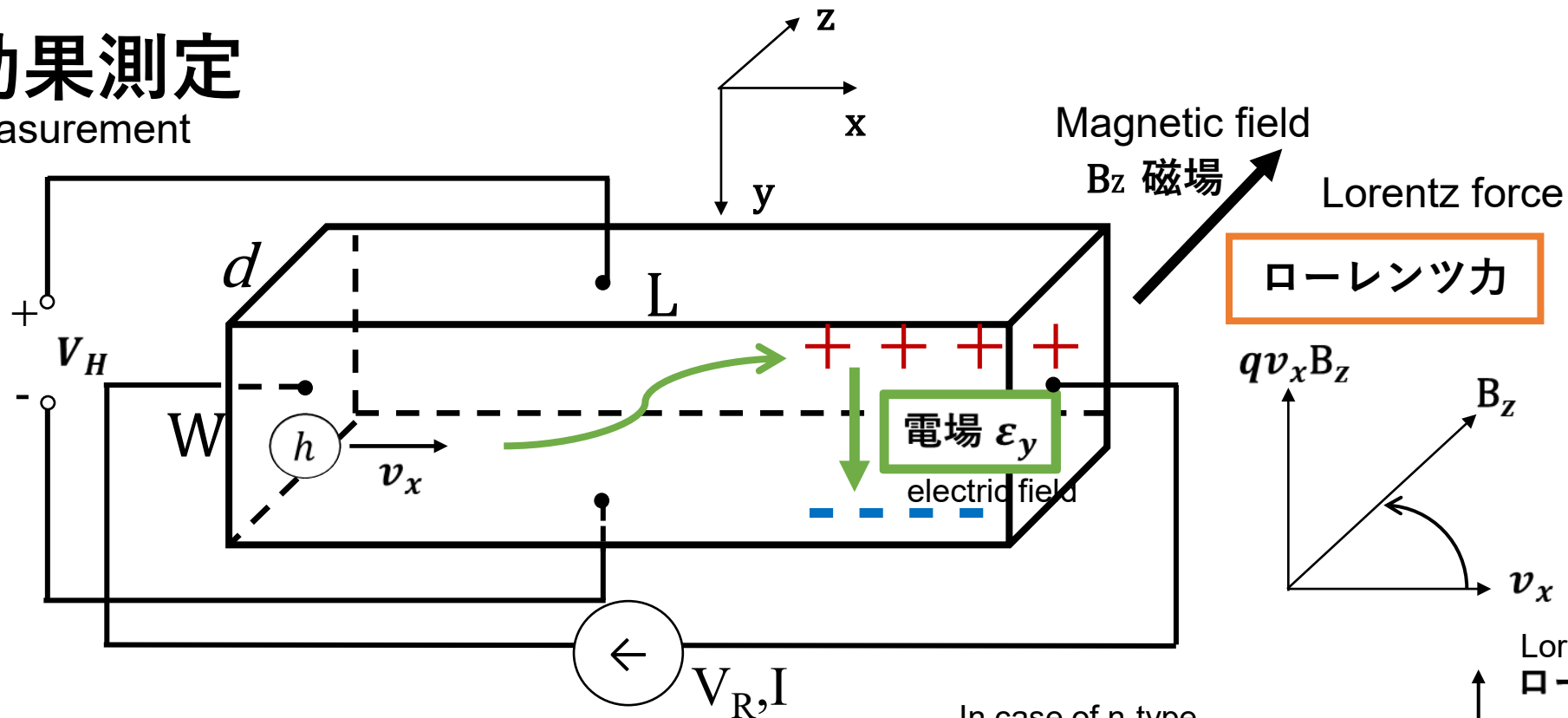
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材料工学科 Department of Materials Science

弓野健太郎 Kentaro Kyuno

ホール効果測定

Hall effect measurement



In case of n-type
 $q\varepsilon_y = qv_x B_z \longrightarrow V_H > 0$ (n型の場合 $V_H < 0$)

$$\varepsilon_y = v_x B_z$$

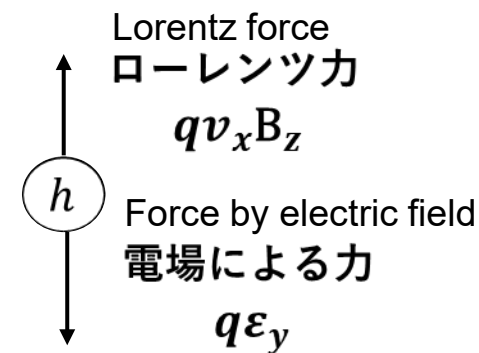
ホール電圧 $V_H = W\varepsilon_y = Wv_x B_z$

Hall voltage

$$I = Av_x \cdot pq \longrightarrow v_x = \frac{I}{Apq} \quad (A = Wd)$$

$$\therefore p = \frac{WIB_z}{AqV_H} = \frac{IB_z}{dqV_H}$$

p can be derived from V_H
 V_H から p が求まる



Exercise 1

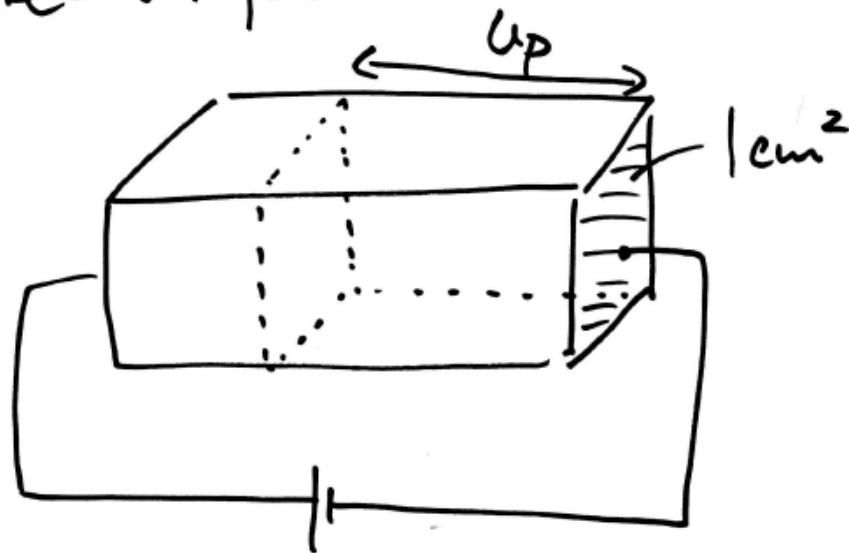
課題 1

Show that the mobility μ can be evaluated by the following expression.

移動度 μ が以下の式で求められることを示せ。

$$\mu = \frac{1}{qp\rho}$$

電流密度. Current density



$$J_p = q \times p \times v_p \quad \leftarrow \mu_p E \quad \text{Hole current}$$

$$J_n = (-q) \times n \times v_n \quad \leftarrow -\mu_n E \quad \text{Electron current}$$

$$J = J_p + J_n = (q p \mu_p + q n \mu_n) \cdot E \propto \frac{J}{E} \quad \sigma: \text{conductivity}$$

resistivity
 $\rho = \frac{1}{\sigma}$
 $(\Omega \cdot \text{cm})$

resistance
 $R = \rho \cdot \frac{l}{S} (\Omega)$



Exercise 2

$I = A v_x \cdot p$

μE (field in x direction)
 x方向の電場

$\therefore \mu = \frac{I}{8 \cdot p \cdot A E} = \frac{1}{8p} \left(\frac{I L}{V_R d w} \right) = \frac{1}{8p \rho}$

\uparrow $d \times w$ \uparrow V_R / L

\swarrow $\frac{1}{\rho}$

抵抗、resistance

$$R = \frac{V_R}{I}$$

抵抗率、resistivity

$$\rho = \frac{dw}{L} R = \frac{V_R W d}{IL}$$

移動度の算出

Derivation of mobility

Resistivity measurement

抵抗測定

Hall effect measurement

ホール効果測定

$$\rho = \frac{V_R W d}{I L}$$

$$p = \frac{I B_z}{q d |V_H|}$$

$$\mu = \frac{1}{q p \rho}$$

- p or n
- キャリア密度
- 抵抗率
- 移動度

carrier density

resistivity

mobility

半導体における電気伝導

Electrical transport in semiconductors

- ・ドリフト電流 (電場)
- ・拡散電流 (濃度差)

Diffusion current (concentration gradient)

hole
正孔

$$\oplus \xrightarrow{qE \cdot \tau}$$

$$\xrightarrow{E \text{ (電場)}}$$

Mean free time

$$\tau = \frac{1}{\nu}$$

$$qE \cdot \tau = m_p \cdot v_p \quad \leftarrow \text{正孔の移動度}$$

$$v_p = \frac{q\tau}{m_p} \cdot E$$

μ_p hole mobility
正孔の移動度

Hole velocity

電子 electron

$$\xleftarrow{-q \cdot E} \ominus$$

$$\xrightarrow{E}$$

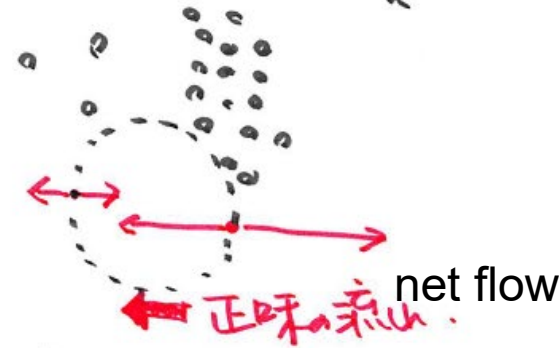
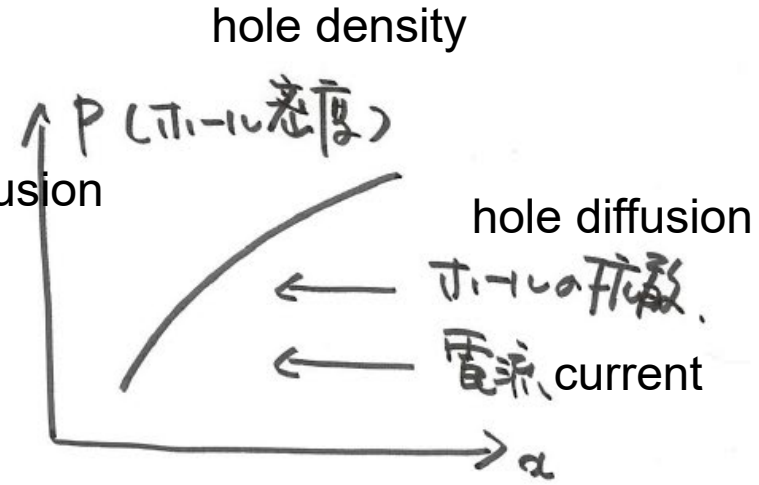
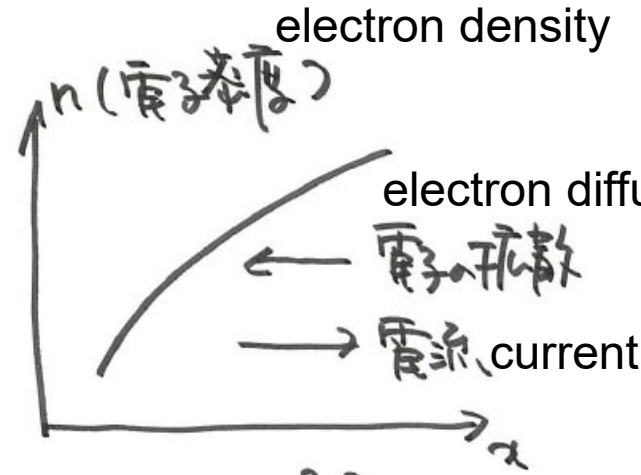
$$-qE \cdot \tau = m_n \cdot v_n$$

$$\therefore v_n = -\frac{q\tau}{m_n} \cdot E$$

μ_n electron mobility
電子の移動度

拡散電流

Diffusion current



hole diffusivity

正孔の拡散係数

$$J_n, \text{diffusion} = -D_n \frac{dn}{dx}$$

$$J_p, \text{diffusion} = -D_p \frac{dp}{dx}$$

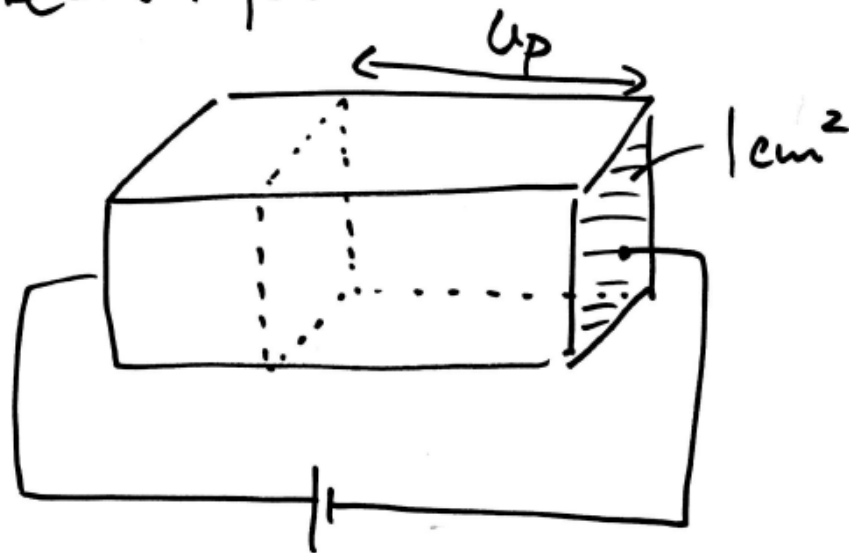
$$J_n, \text{diffusion} = (-q) \cdot (-D_n \frac{dn}{dx})$$

$$J_p, \text{diffusion} = q \cdot (-D_p \frac{dp}{dx})$$

$$\begin{aligned} \therefore J_n &= J_{n, \text{drift}} + J_{n, \text{diffusion}} = q n \mu_n E + q D_n \frac{dn}{dx} \\ J_p &= J_{p, \text{drift}} + J_{p, \text{diffusion}} = q p \mu_p E - q D_p \frac{dp}{dx} \end{aligned}$$

$$J = J_n + J_p$$

電流密度. Current density



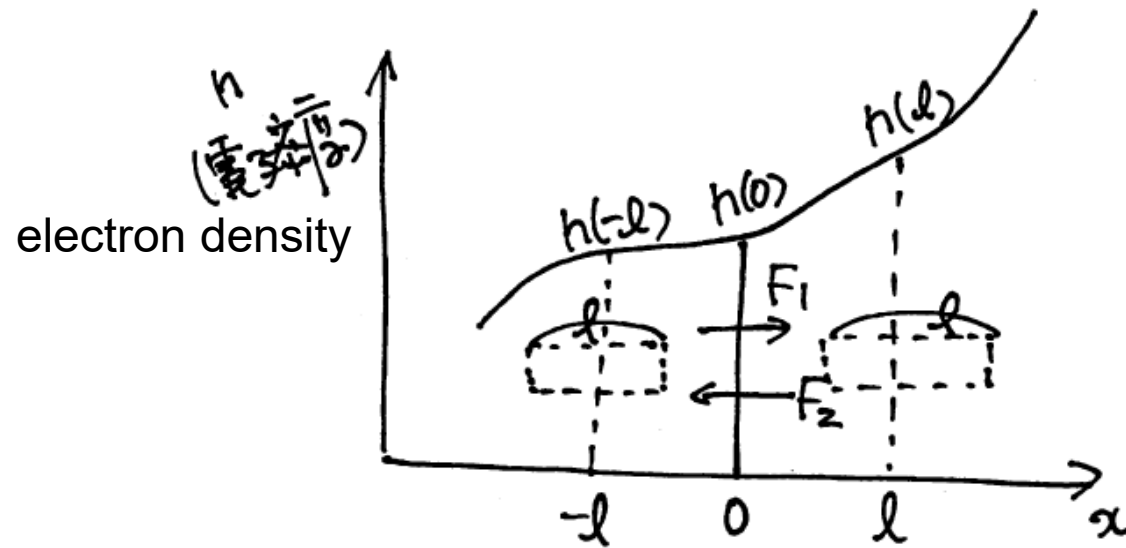
$$J_p = q \times p \times v_p \quad \leftarrow \mu_p E \quad \text{ホールの電流. Hole current}$$

$$J_n = (-q) \times n \times v_n \quad \leftarrow -\mu_n E \quad \text{電子の電流. Electron current}$$

$$J = J_p + J_n = (q p \mu_p + q n \mu_n) \cdot E \propto \frac{\text{電流}}{\text{電場}} \quad \sigma: \text{conductivity}$$

resistivity
抵抗率.
 $\rho = \frac{1}{\sigma} \quad (\Omega \cdot \text{cm})$

resistance
抵抗
 $R = \rho \cdot \frac{l}{S} (\Omega)$



$$\begin{cases} F_1 = \frac{\frac{1}{2} n(-l) \cdot l}{\tau_c} = \frac{1}{2} n(-l) \cdot v_{th} & (\because l = v_{th} \cdot \tau_c) \\ F_2 = \frac{1}{2} n(l) \cdot v_{th} \end{cases}$$

正味の流れ
net flow

$$F = F_1 - F_2 = \frac{1}{2} v_{th} [n(-l) - n(l)]$$

$$= - v_{th} \cdot l \left. \frac{dn}{dx} \right|_{x=0}$$

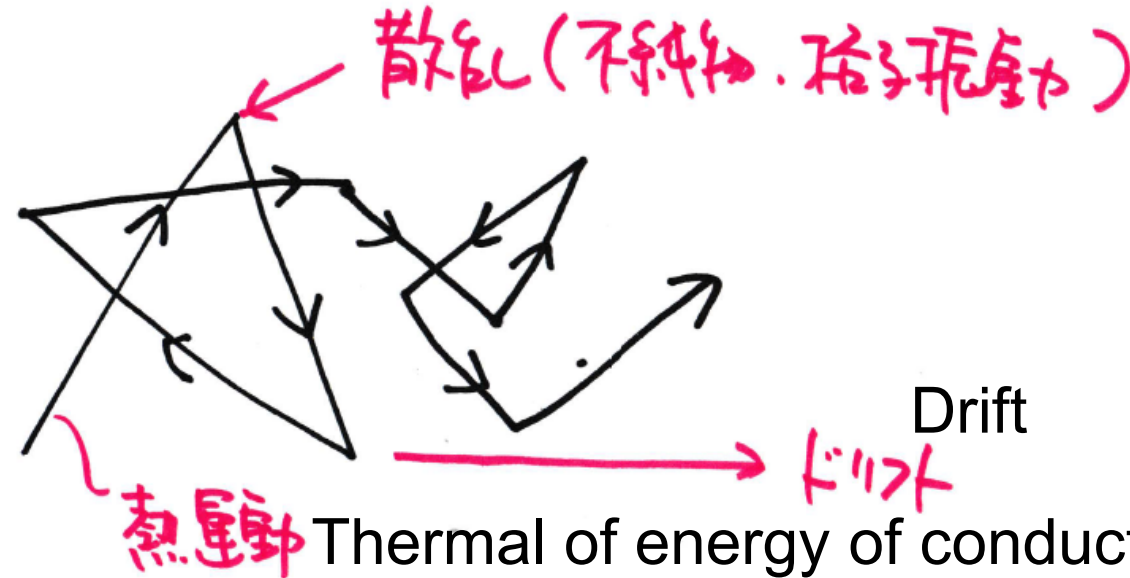
D_n 拡散係数

electron diffusivity

Drift current

ドリフト電流

Scattering (impurity, lattice vibration)

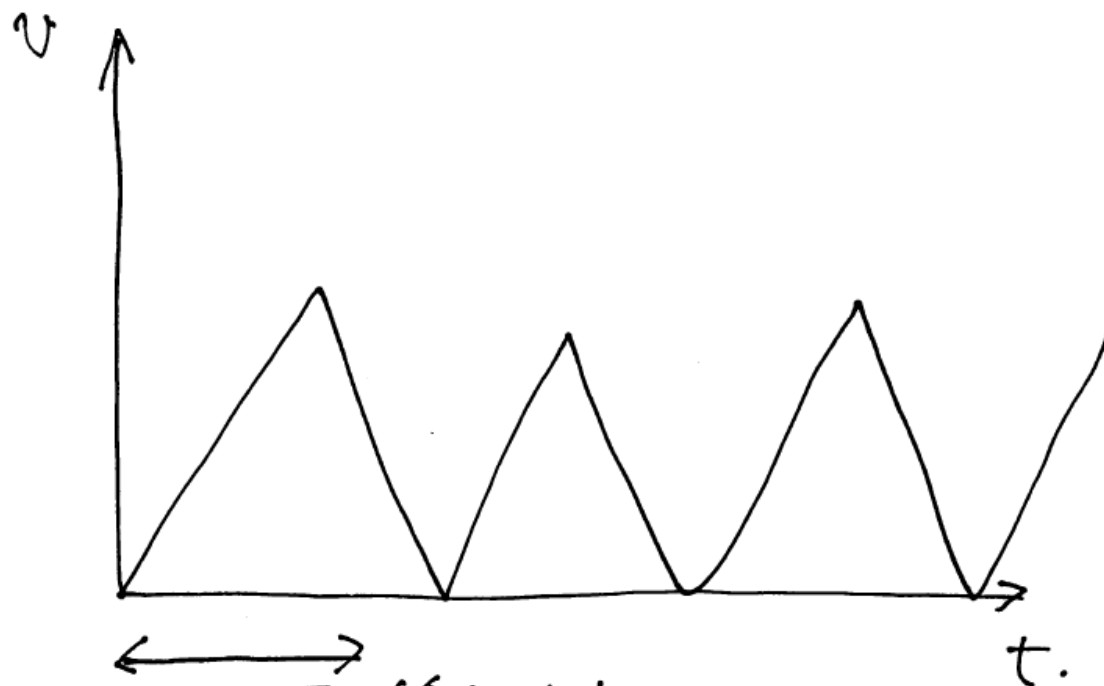


Thermal energy of conduction electron

$$\frac{1}{2}mv^2 = \frac{3}{2}kT$$

m: electron mass, v: electron velocity, k: Boltzmann constant
T: absolute temperature

$$v = \sqrt{\frac{3kT}{m}} = \sqrt{\frac{3 \times 1.38 \times 10^{-23} \times 300}{9.11 \times 10^{-31}}} = 1.2 \times 10^5 \text{ m/s}$$



τ_c 平均緩和時間 Mean free time
 $\sim 1\text{ps} = 10^{-12}\text{s}$

$\tau_c \cdot v_{th} = l$ 平均自由行程 Mean free path
 $\sim 10^{-5}\text{cm.}$

\uparrow
 熱速度
 Thermal velocity

hole
正孔

$$\oplus \xrightarrow{qE \cdot \tau}$$

$$\xrightarrow{E \text{ (電場)}}$$

Mean free time

$$\text{自由時間} = \tau$$

$$qE \cdot \tau = m_p \cdot v_p \quad \leftarrow \text{正孔の移動速度}$$

$$v_p = \frac{q\tau}{m_p} \cdot E$$

μ_p hole mobility
正孔の移動度

Hole velocity

電子 electron

$$\xleftarrow{-q \cdot E} \ominus$$

$$\xrightarrow{E}$$

$$-qE \cdot \tau = m_n \cdot v_n$$

$$\therefore v_n = -\frac{q\tau}{m_n} \cdot E$$

μ_n electron mobility
電子の移動度

アインシュタインの関係式 Einstein relation

← $\frac{kT}{q}$ absolute temperature

law of equipartition of energy
エネルギー等分配則

$$\frac{1}{2} m_n v_{th}^2 = \frac{1}{2} kT$$

↑
電子の
質量

↑
熱速度

thermal velocity

electron mass

electron mobility

↓
電子の移動度

$$D_n = v_{th} \cdot l = v_{th} \cdot (v_{th} \tau_c)$$

$$= v_{th}^2 \cdot \left(\frac{\mu_n m_n}{q} \right)$$

$$= \frac{kT}{m_n} \cdot \frac{\mu_n m_n}{q}$$

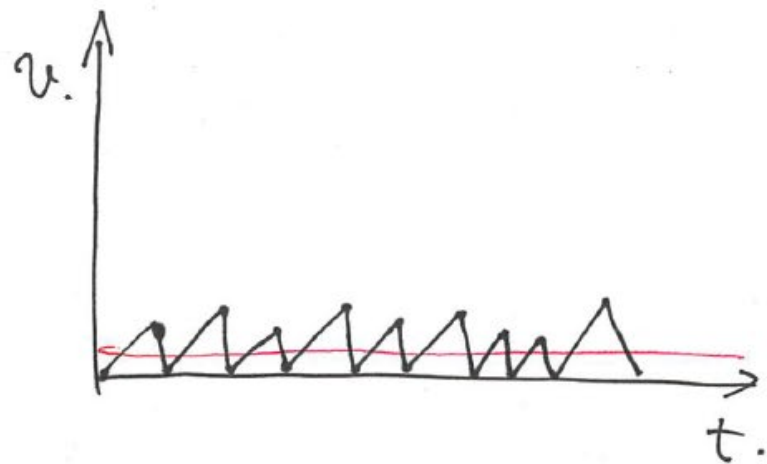
$$\therefore \mu_n = \frac{q \tau_c}{m_n}$$

$$\therefore D_n = \left(\frac{kT}{q} \right) \cdot \mu_n$$

ドリフト Drift

mean free time, mean free path ~ small

$\tau_c, l \ll$



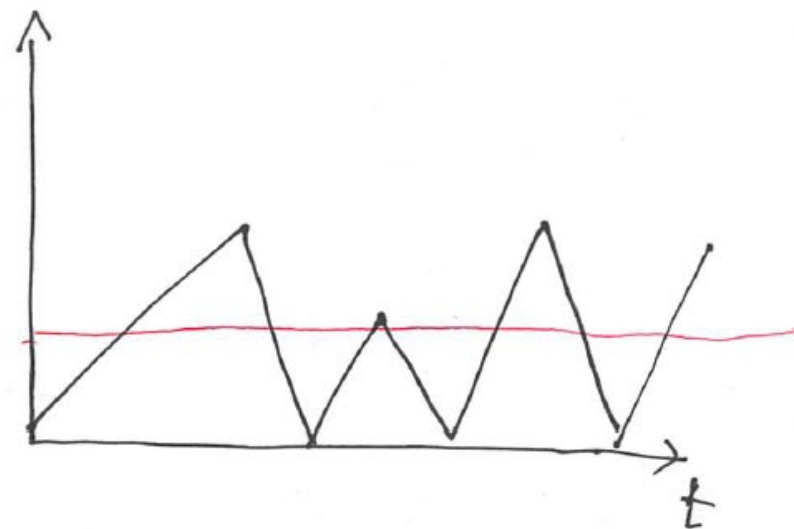
$\mu \ll$

移動度

mobility ~ small

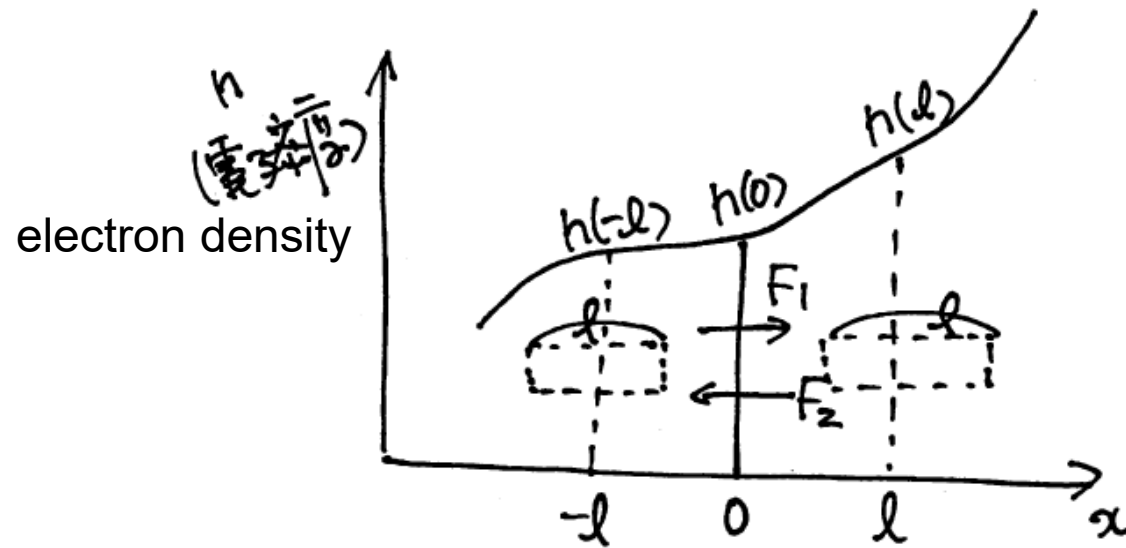
mean free time, mean free path ~ large

$\tau_c, l \gg$



$\mu \gg$

mobility ~ large



$$\begin{cases} F_1 = \frac{\frac{1}{2} n(-l) \cdot l}{\tau_c} = \frac{1}{2} n(-l) \cdot v_{th} & (\because l = v_{th} \cdot \tau_c) \\ F_2 = \frac{1}{2} n(l) \cdot v_{th} \end{cases}$$

正味の流れ
net flow

$$F = F_1 - F_2 = \frac{1}{2} v_{th} [n(-l) - n(l)]$$

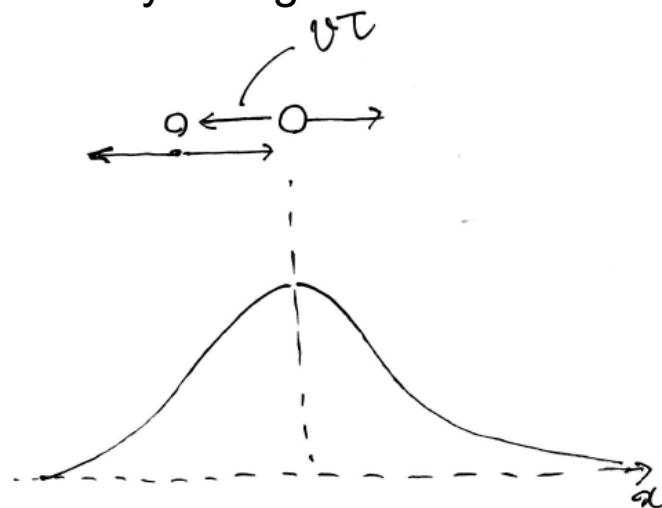
$$= - \underbrace{v_{th} \cdot l}_{D_n} \frac{dn}{dx} \bigg|_{x=0}$$

D_n 拡散係数

electron diffusivity

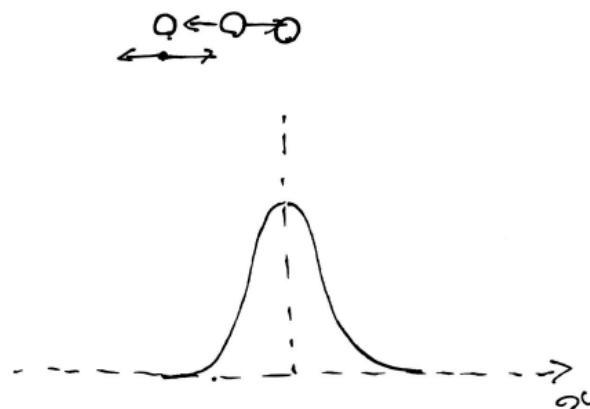
扩散. Diffusion

diffusivity ~ large



mean free time, mean free path ~ large
 τ

diffusivity ~ small



mean free time, mean free path ~ small
 τ

演習 1

n型半導体において、0.1cmの間で電子密度が 1×10^{18} から $7 \times 10^{17} \text{ cm}^{-3}$ へと直線的に変化している。
このときの拡散電流を計算せよ。
ただし、拡散係数を $22.5 \text{ cm}^2/\text{s}$ とする。

Exercise 1

Assume that, in an n-type semiconductor, the electron concentration varies linearly from 1×10^{18} to $7 \times 10^{17} \text{ cm}^{-3}$ over a distance of 0.1cm. Calculate the diffusion current assuming that the electron diffusivity is $22.5 \text{ cm}^2/\text{s}$.

演習 2

少数キャリア（ホール）が均一なn型半導体の一点に注入されているとする。この試料に50V/cmの電界をかけたところ、この電界によって少数キャリアが100 μ sの間に1cm移動したとする。

このとき、少数キャリアのドリフト速度、移動度、拡散係数を求めよ。ただし、 $T=300\text{K}$ とする。

Exercise 2

Minority carriers (holes) are injected into a homogeneous n-type semiconductor sample at one point. An electric field of 50V/cm is applied across the sample. As a result, the field moves these carriers a distance of 1cm in 100 μ s. Find the drift velocity, mobility and diffusivity of these carriers.